



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Andreas et al.

Serial No.: 10/645,710

Filed: August 21, 2003

For: WAFER CLEANING METHOD AND
RESULTING WAFER

Confirmation No.: 8457

Examiner: Tu Tu V. Ho

Group Art Unit: 2818

Attorney Docket No.: 2269-5663US
(02-1325.00/US)

Notice of Allowance Mailed:

January 26, 2005

CERTIFICATE OF MAILING

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February 25, 2005
Date

Leah J. Barrow
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AMENDMENT PURSUANT TO 37 C.F.R. § 1.312(a)

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Commissioner for Patents
P.O. Box 1450
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Tf
Sir:

Please amend the above-referenced application as follows:

Amendments to the Specification begin on page 3 of this paper.



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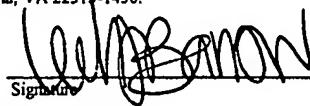
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COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Mail Stop Issue Fee
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

note R
06/22/05
TR
The Examiner indicates:

The prior art of record fails to teach or render obvious a method of cleaning a semiconductor wafer including at least one registration mark having all exclusive limitations as recited in claims 1, 19, and 30, comprising providing a semiconductor wafer comprising at least one registration mark and exposing the semiconductor wafer to a cleaning solution, the at least one registration mark comprising at least one trench having a trench width from approximately 1.0 μm to approximately 3.0 μm , the cleaning solution either comprising tetramethylammonium hydroxide and at least one surfactant, the at least one surfactant as recited in claims 1 and 19, or the cleaning solution consisting essentially of tetramethylammonium hydroxide and at least one surfactant, the at least one surfactant comprising at least one acetylenic diol surfactant.